Jean-François Pierson

List of Publications by Year in descending order

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#	Article	IF	CITATIONS
1	A revised interpretation of the mechanisms governing low friction tribolayer formation in alloyed-TMD self-lubricating coatings. Applied Surface Science, 2022, 571, 151302.	6.1	5
2	Effects of deposition parameters on the microstructure and mechanical properties of Ti(C,N) produced by moderate temperature chemical vapor deposition (MT-CVD) on cemented carbides. Vacuum, 2022, 195, 110650.	3.5	11
3	Tailor the antibacterial efficiency of copper alloys by oxidation: when to and when not to. Journal of Materials Science, 2022, 57, 3807-3821.	3.7	3
4	Influence of the nucleation surface on the growth of epitaxial Al2O3 thermal CVD films deposited on cemented carbides. Materials and Design, 2022, 216, 110601.	7.0	5
5	High-Density Nanowells Formation in Ultrafast Laser-Irradiated Thin Film Metallic Glass. Nano-Micro Letters, 2022, 14, 103.	27.0	8
6	Electrical properties of zinc nitride and zinc tin nitride semiconductor thin films toward photovoltaic applications. High Temperature Materials and Processes, 2022, 41, 343-352.	1.4	3
7	Theoretical and experimental approaches for the determination of functional properties of MgSnN2 thin films. Solar Energy Materials and Solar Cells, 2022, 244, 111797.	6.2	6
8	Nickel doped copper oxide thin films prepared by radiofrequency reactive sputtering: study of the impact of nickel content on the structural, optical and electrical properties. Spectroscopy Letters, 2021, 54, 487-494.	1.0	18
9	Effect of nitrogen vacancies on the growth, dislocation structure, and decomposition of single crystal epitaxial (Ti1-xAlx)Ny thin films. Acta Materialia, 2021, 203, 116509.	7.9	18
10	Composition-driven transition from amorphous to crystalline films enables bottom-up design of functional surfaces. Applied Surface Science, 2021, 538, 148133.	6.1	8
11	Thermal stability of oxygen vacancy stabilized zirconia (OVSZ) thin films. Surface and Coatings Technology, 2021, 409, 126880.	4.8	3
12	ZrCuAg Thin-Film Metallic Glasses: Toward Biostatic Durable Advanced Surfaces. ACS Applied Materials & Interfaces, 2021, 13, 17062-17074.	8.0	18
13	Initial Morphology and Feedback Effects on Laser-Induced Periodic Nanostructuring of Thin-Film Metallic Glasses. Nanomaterials, 2021, 11, 1076.	4.1	11
14	Binary copper oxides as photovoltaic absorbers: recent progress in materials and applications. Journal Physics D: Applied Physics, 2021, 54, 263002.	2.8	12
15	Growth kinetics and origin of residual stress of two-phase crystalline–amorphous nanostructured films. Journal of Applied Physics, 2021, 129, .	2.5	5
16	Surface morphology-optical properties relationship in thermochromic VO2 thin films obtained by air oxidation of vanadium nitride. Journal of Materiomics, 2021, 7, 657-664.	5.7	5
17	Approaching Theoretical Band Gap of ZnSnN ₂ Films via Bias Magnetron Cosputtering at Room Temperature. ACS Applied Electronic Materials, 2021, 3, 3855-3866.	4.3	7
18	Elaboration of high-transparency ZnO thin films by ultrasonic spray pyrolysis with fast growth rate. Superlattices and Microstructures, 2021, 156, 106945.	3.1	7

Jean-François Pierson

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19	Real-time high-temperature scanning indentation: Probing physical changes in thin-film metallic glasses. Applied Materials Today, 2021, 24, 101126.	4.3	2
20	Optical and electrical properties of hard (Hf,Nb,Ti,V,Zr)Nx thin films. Vacuum, 2021, 193, 110517.	3.5	4
21	Blue emission and twin structure of p-type copper iodide thin films. Surfaces and Interfaces, 2021, 27, 101500.	3.0	6
22	Effect of Thermal Stresses Formed during Air Annealing of Amorphous Lanthanum Cuprate Thin Films Deposited on Silicon Substrate. Coatings, 2020, 10, 613.	2.6	7
23	Sodium chloride assists copper release, enhances antibacterial efficiency, and introduces atmospheric corrosion on copper surface. Surfaces and Interfaces, 2020, 20, 100630.	3.0	2
24	Preparation and characterization of nanocomposite of Co:CuO by radio-frequency sputtering for solar selective absorber application. Thin Solid Films, 2020, 709, 138199.	1.8	16
25	Oxidation of sputter-deposited vanadium nitride as a new precursor to achieve thermochromic VO2 thin films. Solar Energy Materials and Solar Cells, 2020, 210, 110474.	6.2	11
26	Insights into the wear track evolution with sliding cycles of carbon-alloyed transition metal dichalcogenide coatings. Surface and Coatings Technology, 2020, 403, 126360.	4.8	9
27	Growth and high temperature decomposition of epitaxial metastable wurtzite (Ti1-x,Alx)N(0001) thin films. Thin Solid Films, 2019, 688, 137414.	1.8	8
28	Controlling surface morphology by nanocrystalline/amorphous competitive self-phase separation in thin films: Thickness-modulated reflectance and interference phenomena. Acta Materialia, 2019, 181, 78-86.	7.9	11
29	Bacteria accumulate copper ions and inhibit oxide formation on copper surface during antibacterial efficiency test. Micron, 2019, 127, 102759.	2.2	10
30	Semi-Transparent p-Cu ₂ O/n-ZnO Nanoscale-Film Heterojunctions for Photodetection and Photovoltaic Applications. ACS Applied Nano Materials, 2019, 2, 4358-4366.	5.0	49
31	Dislocation structure and microstrain evolution during spinodal decomposition of reactive magnetron sputtered heteroepixatial c-(Ti0.37,Al0.63)N/c-TiN films grown on MgO(001) and (111) substrates. Journal of Applied Physics, 2019, 125, .	2.5	12
32	Localised corrosion attacks and oxide growth on copper in phosphate-buffered saline. Materials Characterization, 2019, 158, 109985.	4.4	14
33	Suppressing the carrier concentration of zinc tin nitride thin films by excess zinc content and low temperature growth. Applied Physics Letters, 2019, 115, .	3.3	14
34	Early-stage corrosion, ion release, and the antibacterial effect of copper and cuprous oxide in physiological buffers: Phosphate-buffered saline vs Na-4-(2-hydroxyethyl)-1-piperazineethanesulfonic acid. Biointerphases, 2019, 14, 061004.	1.6	4
35	Growth, interfacial microstructure and optical properties of NiO thin films with various types of texture. Acta Materialia, 2019, 164, 648-653.	7.9	24
36	The effect of nitrogen vacancies on initial wear in arc deposited (Ti0.52,Al0.48)Ny, (yâ€<â€1) coatings during machining. Surface and Coatings Technology, 2019, 358, 452-460.	4.8	11

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37	Evolution of the structural, morphological, optical and electrical properties of reactively RF-sputtered cobalt oxide thin films with oxygen pressure. Vacuum, 2019, 159, 346-352.	3.5	26
38	Room temperature fabrication of transparent p-NiO/n-ZnO junctions with tunable electrical properties. Vacuum, 2018, 149, 331-335.	3.5	8
39	Chemical environment and functional properties of highly crystalline ZnSnN2 thin films deposited by reactive sputtering at room temperature. Solar Energy Materials and Solar Cells, 2018, 182, 30-36.	6.2	34
40	Wurtzite CoO: a direct band gap oxide suitable for a photovoltaic absorber. Chemical Communications, 2018, 54, 13949-13952.	4.1	21
41	Tunable Localized Surface Plasmon Resonance and Broadband Visible Photoresponse of Cu Nanoparticles/ZnO Surfaces. ACS Applied Materials & Interfaces, 2018, 10, 40958-40965.	8.0	26
42	Local Structure and Point-Defect-Dependent Area-Selective Atomic Layer Deposition Approach for Facile Synthesis of p-Cu ₂ O/n-ZnO Segmented Nanojunctions. ACS Applied Materials & Interfaces, 2018, 10, 37671-37678.	8.0	17
43	Local Homoepitaxial Growth in Sputtered NiO Thin Films: An Effective Approach to Tune the Crystallization, Preferred Growth Orientation, and Electrical Properties. Physica Status Solidi - Rapid Research Letters, 2018, 12, 1800191.	2.4	2
44	Nitrogen chemical state in N-doped Cu2O thin films. Applied Physics Letters, 2017, 110, .	3.3	18
45	Infrared Plasmonics with Conductive Ternary Nitrides. ACS Applied Materials & Interfaces, 2017, 9, 10825-10834.	8.0	42
46	Room temperature self-assembled growth of vertically aligned columnar copper oxide nanocomposite thin films on unmatched substrates. Scientific Reports, 2017, 7, 11122.	3.3	7
47	Structural and mechanical properties of Zr1â ^{~*} x Mox thin films: From the nano-crystalline to the amorphous state. Journal of Alloys and Compounds, 2017, 729, 137-143.	5.5	5
48	Inductive Effect of Nd for Ni ³⁺ Stabilization in NdNiO ₃ Synthesized by Reactive DC Cosputtering. Journal of Physical Chemistry C, 2017, 121, 21579-21590.	3.1	11
49	Enhanced thermal stability and mechanical properties of nitrogen deficient titanium aluminum nitride (Ti0.54Al0.46Ny) thin films by tuning the applied negative bias voltage. Journal of Applied Physics, 2017, 122, .	2.5	17
50	Atypical Properties of FIB-Patterned RuO _{<i>x</i>} Nanosupercapacitors. ACS Energy Letters, 2017, 2, 1734-1739.	17.4	25
51	Optical and electronic properties of conductive ternary nitrides with rare- or alkaline-earth elements, Journal of Applied Physics, 2016, 120, . Electronic structures of mmi:math	2.5	14
52	xmlns:mml="http://www.w3.org/1998/Math/MathML"> <mml:mrow><mml:mi mathvariant="normal">C<mml:msub><mml:mi mathvariant="normal">u<mml:mn>2</mml:mn></mml:mi </mml:msub><mml:mi mathvariant="normal">Q<mml:mo>,</mml:mo><mml:mi< td=""><td>3.2</td><td>202</td></mml:mi<></mml:mi </mml:mi </mml:mrow>	3.2	202
53	mathvariant="normal">C <mml:msub><mml:mi mathvariant="normal">u<mml:mn>4 Phenomenological study of Iron and lanthanum magnetron co-sputtering using two reactive gases. Surface and Coatings Technology, 2016, 298, 39-44.</mml:mn></mml:mi </mml:msub>	4.8	13
54	E-MRS 2015 Symposium EE: Protective coatings and thin films. Surface and Coatings Technology, 2016, 295, 1.	4.8	0

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55	Role of Cu ⁺ on ZnS:Cu p-type semiconductor films grown by sputtering: influence of substitutional Cu in the structural, optical and electronic properties. RSC Advances, 2016, 6, 43480-43488.	3.6	19
56	Comparative Study of Sliding, Scratching, and Impact-Loading Behavior of Hard CrB2 and Cr–B–N Films. Tribology Letters, 2016, 63, 1.	2.6	29
57	Innovative Smart Selective Coating to Avoid Overheating in Highly Efficient Thermal Solar Collectors. Energy Procedia, 2016, 91, 84-93.	1.8	31
58	Local heteroepitaxial growth to promote the selective growth orientation, crystallization and interband transition of sputtered NiO thin films. CrystEngComm, 2016, 18, 1732-1739.	2.6	8
59	Substrate Temperature Influenced Structural and Optical Properties of RF Sputtered Ag–Cu–O Films. Advanced Science Letters, 2016, 22, 51-55.	0.2	0
60	Towards delafossite structure of Cu–Cr–O thin films deposited by reactive magnetron sputtering: Influence of substrate temperature onÂoptoelectronics properties. Vacuum, 2015, 114, 101-107.	3.5	22
61	Structural investigations of iron oxynitride multilayered films obtained by reactive gas pulsing process. Surface and Coatings Technology, 2015, 272, 158-164.	4.8	8
62	Tuning the structure and preferred orientation in reactively sputtered copper oxide thin films. Applied Surface Science, 2015, 335, 85-91.	6.1	44
63	Electrochemical reaction of lithium with ruthenium nitride thin films prepared by pulsed-DC magnetron sputtering. Electrochimica Acta, 2015, 164, 12-20.	5.2	18
64	Two anode materials for Li ion batteries with different reaction mechanisms : silicon nanowires and ruthenium nitride thin film. , 2014, , .		0
65	Characterization of Silver Oxide Films Formed by Reactive RF Sputtering at Different Substrate Temperatures. , 2014, 2014, 1-7.		37
66	Transmittance enhancement and optical band gap widening of Cu2O thin films after air annealing. Journal of Applied Physics, 2014, 115, .	2.5	85
67	Comparative analysis of Cr-B coatings deposited by magnetron sputtering in DC and HIPIMS modes. Technical Physics Letters, 2014, 40, 614-617.	0.7	11
68	Hard Cr–Al–Si–B–(N) coatings deposited by reactive and non-reactive magnetron sputtering of CrAlSiB target. Applied Surface Science, 2014, 314, 104-111.	6.1	44
69	VN thin films as electrode materials for electrochemical capacitors. Electrochimica Acta, 2014, 141, 203-211.	5.2	98
70	Mechanisms of Oxidation of NdNiO _{3â~Î~} Thermochromic Thin Films Synthesized by a Two-Step Method in Soft Conditions. Journal of Physical Chemistry C, 2014, 118, 5908-5917.	3.1	15
71	Controlling the preferred orientation in sputter-deposited Cu2O thin films: Influence of the initial growth stage and homoepitaxial growth mechanism. Acta Materialia, 2014, 76, 207-212.	7.9	30
72	Physical Behaviour of RF Magnetron Sputtered Ag2Cu2O3 Films: Influence of Oxygen Partial Pressure and Substrate Temperature. Advanced Science Letters, 2014, 20, 946-952.	0.2	0

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73	Tribocorrosion behavior of Ti–C–O–N nanostructured thin films (black) for decorative applications. Tribology International, 2013, 68, 1-10.	5.9	6
74	Application of sputtered ruthenium nitride thin films as electrode material for energy-storage devices. Scripta Materialia, 2013, 68, 659-662.	5.2	85
75	Cation size effect on the thermochromic properties of rare earth cobaltites <i>RE</i> CoO ₃ (<i>RE</i> : La, Nd, Sm). Journal of Applied Physics, 2013, 114, 113510.	2.5	13
76	Asymmetric electrochemical capacitor microdevice designed with vanadium nitride and nickel oxide thin film electrodes. Electrochemistry Communications, 2013, 28, 104-106.	4.7	93
77	Vibrational Properties of CuO and Cu ₄ O ₃ from First-Principles Calculations, and Raman and Infrared Spectroscopy. Journal of Physical Chemistry C, 2012, 116, 10232-10237.	3.1	417
78	Thermochromic effect at room temperature of Sm0.5Ca0.5MnO3 thin films. Journal of Applied Physics, 2012, 111, 113517.	2.5	7
79	Efficient, Low Cost Synthesis of Sodium Platinum Bronze Na _{<i>x</i>} Pt ₃ O ₄ . Chemistry of Materials, 2012, 24, 2429-2432.	6.7	6
80	Structural, surface morphological, and optical properties of nanocrystalline Cu ₂ O and CuO films formed by RF magnetron sputtering: Oxygen partial pressure effect. Physica Status Solidi (A) Applications and Materials Science, 2012, 209, 1279-1286.	1.8	26
81	Bacterial adhesion on biomedical surfaces covered by micrometric silver Islands. Journal of Biomedical Materials Research - Part A, 2012, 100A, 1521-1528.	4.0	10
82	High hardness, low Young's modulus and low friction of nanocrystalline ZrW2 Laves phase and Zr1â^'xWx thin films. Journal of Physics and Chemistry of Solids, 2012, 73, 554-558.	4.0	14
83	Process-Parameter-Dependent Structural, Electrical, and Optical Properties of Reactive Magnetron Sputtered Ag-Cu-O Films. Journal of Nanotechnology, 2011, 2011, 1-8.	3.4	5
84	Chemistry, phase formation, and catalytic activity of thin palladium-containing oxide films synthesized by plasma-assisted physical vapor deposition. Surface and Coatings Technology, 2011, 205, S171-S177.	4.8	33
85	Effect of the deposition process on the composition and structure of sputtered lanthanum cuprate films. Surface and Coatings Technology, 2011, 205, S254-S257.	4.8	4
86	Structure and chemical bonds in reactively sputtered black Ti–C–N–O thin films. Thin Solid Films, 2011, 520, 144-151.	1.8	20
87	Hard Cr-Al-Si-B-(N) coatings with oxidation resistance up to 1200°C. Glass Physics and Chemistry, 2011, 37, 411-417.	0.7	11
88	The effect of oxygen partial pressure on physical properties of nanoâ€crystalline silver oxide thin films deposited by RF magnetron sputtering. Crystal Research and Technology, 2011, 46, 961-966.	1.3	8
89	Growth, electrical and optical behaviour of nanocrystalline Ag ₂ Cu ₂ O ₃ films produced by RF magnetron sputtering. Crystal Research and Technology, 2011, 46, 1329-1336.	1.3	0
90	Development of novel titanium nitride-based decorative coatings by calcium addition. Applied Surface Science, 2011, 257, 8525-8528.	6.1	12

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91	Influence of the nanoscale structural features on the properties and electronic structure of Al-doped ZnO thin films: An X-ray absorption study. Solar Energy Materials and Solar Cells, 2011, 95, 2341-2346.	6.2	35
92	Self supported nickel antimonides based electrodes for Li ion battery. Solid State Ionics, 2011, 192, 298-303.	2.7	19
93	Oxidation resistance of decorative (Ti,Mg)N coatings deposited by hybrid cathodic arc evaporation-magnetron sputtering process. Surface and Coatings Technology, 2011, 205, 4547-4553.	4.8	23
94	Effect of substrate temperature on the structural, electrical and optical behaviour of reactively sputtered Ag–Cu–O films. Physica Scripta, 2011, 84, 045602.	2.5	4
95	OXYGEN PARTIAL PRESSURE AND SUBSTRATE BIAS VOLTAGE INFLUENCED STRUCTURAL, ELECTRICAL AND OPTICAL PROPERTIES OF RF MAGNETRON SPUTTERED Ag2Cu2O3 FILMS. International Journal of Nanoscience, 2011, 10, 653-657.	0.7	1
96	Structural, Electrical and Optical Behaviour of RF Magnetron Sputtered Nanocrystalline Silver Oxide Films: Bias Effect. , 2011, , .		1
97	Antibacterial properties of biomedical surfaces containing micrometric silver islands. Journal of Physics: Conference Series, 2010, 252, 012015.	0.4	2
98	Substrate temperature influenced structural, electrical and optical properties of dc magnetron sputtered MoO3 films. Applied Surface Science, 2010, 256, 3133-3137.	6.1	44
99	EPMA–EDS surface measurements of interdiffusion coefficients between miscible metals in thin films. Applied Surface Science, 2010, 256, 1855-1860.	6.1	8
100	Effect of deposition temperature on the physical properties of RF magnetron sputtered Ag–Cu–O films with various Cu to Ag ratios. Physica Status Solidi (A) Applications and Materials Science, 2010, 207, 1655-1659.	1.8	8
101	Structure and Chemical Bonds in Black Ti(C, N, O) Thin Films. , 2010, , .		0
102	Influence of substrate temperature on the structural, dielectric and optical properties of RF magnetron sputtered Ta ₂ O ₅ films. IOP Conference Series: Materials Science and Engineering, 2010, 8, 012025.	0.6	5
103	On the deactivation of the dopant and electronic structure in reactively sputtered transparent Al-doped ZnO thin films. Journal Physics D: Applied Physics, 2010, 43, 132003.	2.8	34
104	Impact of the particles impingement on the electronic conductivity of Al doped ZnO films grown by reactive magnetron sputtering. IOP Conference Series: Materials Science and Engineering, 2010, 12, 012006.	0.6	0
105	Evolution of structural and physical properties upon annealing of sputter-deposited Zr0.84Y0.16-O2films incorporating copper and palladium nanoparticles. IOP Conference Series: Materials Science and Engineering, 2009, 5, 012022.	0.6	0
106	Thermochromic effect in NdNiO3â^îîthin films annealed in ambient air. Journal Physics D: Applied Physics, 2009, 42, 182006.	2.8	15
107	Arc-evaporated nanocomposite zirconium-based boronitride coatings. Materials Chemistry and Physics, 2009, 114, 780-784.	4.0	8
108	Strontium-doped lanthanum manganite coatings crystallised after air annealing of amorphous co-sputtered films. Materials Chemistry and Physics, 2009, 116, 219-222.	4.0	7

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109	Structure Control in Reactively Sputtered Ag/Cu/(Mn)/O Films. Plasma Processes and Polymers, 2009, 6, 393-400.	3.0	8
110	Effect of nitrogen partial pressure on the structure, physical and mechanical properties of CrB2 and Cr–B–N films. Thin Solid Films, 2009, 517, 2675-2680.	1.8	40
111	Oxidation and tribo-oxidation of nanocomposite Cr–Si–N coatings deposited by a hybrid arc/magnetron process. Surface and Coatings Technology, 2009, 204, 973-977.	4.8	9
112	Silver islands formed after air annealing of amorphous Ag–Cu–Mn–O sputtered films. Journal of Crystal Growth, 2009, 311, 349-354.	1.5	9
113	Effect of annealing temperature on the decomposition of reactively sputtered Ag2Cu2O3 films. Applied Surface Science, 2009, 255, 7700-7702.	6.1	12
114	Structure–properties relationship in reactively sputtered Ag–Cu–O films. Journal Physics D: Applied Physics, 2009, 42, 025304.	2.8	15
115	Properties of nanocrystalline and nanocomposite WxZr1â^'x thin films deposited by co-sputtering. Intermetallics, 2009, 17, 421-426.	3.9	18
116	Deep oxidation of methane on particles derived from YSZ-supported Pd–Pt-(O) coatings synthesized by Pulsed Filtered Cathodic Arc. Catalysis Communications, 2009, 10, 1410-1413.	3.3	9
117	Comparison Between Ultrathin Films of YSZ Deposited at the Solid Oxide Fuel Cell Cathode/Electrolyte Interface by Atomic Layer Deposition, Dip-Coating or Sputtering. Open Fuels and Energy Science Journal, 2009, 2, 87-99.	0.2	Ο
118	Effect of the oxygen flow rate on the structure and the properties of Ag–Cu–O sputtered films deposited using a Ag/Cu target with eutectic composition. Applied Surface Science, 2008, 254, 6590-6594.	6.1	26
119	Structural-electrical-optical properties relationship of sodium superionic conductor sputter-deposited coatings. Thin Solid Films, 2008, 516, 3387-3393.	1.8	4
120	Towards a thin films electrochromic device using NASICON electrolyte. Ionics, 2008, 14, 227-233.	2.4	8
121	Influence of the nanostructuration of PVD hard TiN-based films on the durability of coated steel. Surface and Coatings Technology, 2008, 202, 2268-2277.	4.8	47
122	Study of the structural changes induced by air oxidation in Ti–Si–N hard coatings. Surface and Coatings Technology, 2008, 202, 2413-2417.	4.8	33
123	Reactive gas pulsing process: A method to extend the composition range in sputtered iron oxynitride films. Surface and Coatings Technology, 2008, 202, 4825-4829.	4.8	17
124	Development of dark Ti(C,O,N) coatings prepared by reactive sputtering. Surface and Coatings Technology, 2008, 203, 804-807.	4.8	24
125	Addition of silver in copper nitride films deposited by reactive magnetron sputtering. Scripta Materialia, 2008, 58, 568-570.	5.2	50
126	Structural properties of iron oxynitride films obtained by reactive magnetron sputtering. Journal of Physics Condensed Matter, 2007, 19, 226207.	1.8	8

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127	Magnetron sputtering of NASICON (Na3Zr2Si2PO12) thin films Part I: Limitations of the classical methods. Surface and Coatings Technology, 2007, 201, 7013-7017.	4.8	5
128	Magnetron sputtering of NASICON (Na3Zr2Si2PO12) thin films. Surface and Coatings Technology, 2007, 201, 7060-7065.	4.8	16
129	Experimental and theoretical contributions to the determination of optical properties of synthetic paramelaconite. Journal of Solid State Chemistry, 2007, 180, 968-973.	2.9	27
130	Use of silane for the deposition of hard and oxidation resistant Ti–Si–N coatings by a hybrid cathodic arc and chemical vapour process. Materials Letters, 2007, 61, 2506-2508.	2.6	15
131	Chemical environment of iron atoms in iron oxynitride films synthesized by reactive magnetron sputtering. Scripta Materialia, 2007, 56, 153-156.	5.2	18
132	Influence of the current applied to the silver target on the structure and the properties of Ag–Cu–O films deposited by reactive cosputtering. Applied Surface Science, 2007, 253, 7522-7526.	6.1	30
133	Influence of the silicon concentration on the optical and electrical properties of reactively sputtered Zr–Si–N nanocomposite coatings. Materials Science and Engineering B: Solid-State Materials for Advanced Technology, 2006, 131, 36-39.	3.5	13
134	Reactive sputtering: A method to modify the metallic ratio in the novel silver–copper oxides. Applied Surface Science, 2006, 253, 1484-1488.	6.1	22
135	Characterization of W–Ge–N coatings deposited by sputtering. Surface and Coatings Technology, 2006, 200, 6303-6307.	4.8	8
136	Oxidation resistance improvement of arc-evaporated TiN hard coatings by silicon addition. Surface and Coatings Technology, 2006, 201, 4158-4162.	4.8	50
137	Investigation of Niobium oxynitride thin films deposited by reactive magnetron sputtering. Surface and Coatings Technology, 2006, 201, 4152-4157.	4.8	35
138	Structure and tribological properties of reactively sputtered Zr–Si–N films. Thin Solid Films, 2006, 496, 445-449.	1.8	24
139	Property change in multifunctional TiCxOy thin films: Effect of the O/Ti ratio. Thin Solid Films, 2006, 515, 866-871.	1.8	45
140	Structural, optical and electrical properties of reactively sputtered iron oxynitride films. Journal Physics D: Applied Physics, 2006, 39, 1894-1898.	2.8	20
141	Reactive magnetron sputtering of copper, silver, and gold. Thin Solid Films, 2005, 478, 196-205.	1.8	172
142	Effect of germanium addition on the properties of reactively sputtered ZrN films. Thin Solid Films, 2005, 492, 180-186.	1.8	18
143	Stability of reactively sputtered silver oxide films. Surface and Coatings Technology, 2005, 200, 276-279.	4.8	102
144	Reactive sputtering of iron in Ar–N2 and Ar–O2 mixtures. Surface and Coatings Technology, 2005, 200, 431-434.	4.8	9

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145	Influence of silicon addition on the oxidation resistance of CrN coatings. Surface and Coatings Technology, 2005, 200, 264-268.	4.8	63
146	Properties and electrochromic performances of reactively sputtered tungsten oxide films with water as reactive gas. Surface and Coatings Technology, 2005, 200, 232-235.	4.8	12
147	Substrate effect on the formation of ω-phase in sputtered zirconium films. Scripta Materialia, 2005, 53, 1031-1036.	5.2	11
148	Structural, electrical, optical, and mechanical characterizations of decorative ZrOxNy thin films. Journal of Applied Physics, 2005, 98, 023715.	2.5	87
149	Amorphous Fe–B–N films deposited by reactive sputtering of a FeB target. Surface and Coatings Technology, 2004, 180-181, 44-48.	4.8	11
150	Structural changes in Zr–Si–N films vs. their silicon content. Surface and Coatings Technology, 2004, 180-181, 352-356.	4.8	62
151	Influence of substrate temperature on titanium oxynitride thin films prepared by reactive sputtering. Applied Surface Science, 2004, 225, 29-38.	6.1	53
152	Stabilisation of tetragonal zirconia in oxidised Zrî—,Siî—,N nanocomposite coatings. Applied Surface Science, 2004, 229, 132-139.	6.1	30
153	Properties of iron boride films prepared by magnetron sputtering. Surface and Coatings Technology, 2003, 174-175, 331-337.	4.8	27
154	Influence of the oxygen flow rate on the properties of reactively sputtered Ti–B–O films. Surface and Coatings Technology, 2003, 174-175, 1145-1150.	4.8	5
155	Reactively sputtered zirconium nitride coatings: structural, mechanical, optical and electrical characteristics. Surface and Coatings Technology, 2003, 174-175, 338-344.	4.8	84
156	Cuprite, paramelaconite and tenorite films deposited by reactive magnetron sputtering. Applied Surface Science, 2003, 210, 359-367.	6.1	224
157	Properties and air annealing of paramelaconite thin films. Materials Letters, 2003, 57, 3676-3680.	2.6	35
158	Influence of Bias Voltage on Copper Nitride Films Deposited by Reactive Sputtering. Surface Engineering, 2003, 19, 67-69.	2.2	7
159	Reactively sputtered Ti–B–N nanocomposite films: correlation between structure and optical properties. Thin Solid Films, 2002, 408, 26-32.	1.8	36
160	Structure and properties of copper nitride films formed by reactive magnetron sputtering. Vacuum, 2002, 66, 59-64.	3.5	117
161	Characterisation of reactively sputtered Ti–B–N and Ti–B–O coatings. Surface and Coatings Technology, 2002, 151-152, 526-530.	4.8	12
162	Structural characterisation of ZrB2/oxides nanocomposite films synthesised in flowing Arî—,BCl3 post-discharges. Applied Surface Science, 2001, 172, 285-294.	6.1	3

#	Article	IF	CITATIONS
163	Structural and electrical properties of sputtered titanium boronitride films. Surface and Coatings Technology, 2001, 142-144, 906-910.	4.8	20
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